

## Local structure of Lu doped in high creep resistant $\text{Al}_2\text{O}_3$

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### Introduction

Addition of small amount of a third element into  $\text{Al}_2\text{O}_3$  ceramic have been extensively studied to improve mechanical properties especially at high temperature. Recent years, Yoshida et al. have found that Lu doping is particularly effective in improving the high-temperature creep resistance of poly crystalline  $\text{Al}_2\text{O}_3$ [1]. TEM observation shows that doped Lu atoms condensed in the grain boundary of  $\text{Al}_2\text{O}_3$ [1]. Local environment around Lu atoms at grain boundary is directly connected to the mechanical properties of Lu-doped  $\text{Al}_2\text{O}_3$ . However, the role of the Lu has not been well understood. In this present work, we study the local structure around Lu atoms obtained by EXAFS.

### Experimental

Mixture of high-purity  $\text{Al}_2\text{O}_3$  and Lu acetate pressed into bars with cemented carbide under a pressure of 33MPa, and isostatically-pressed under a pressure of 100MPa. The pressed mixture was sintered at 1400°C for 2 hour in air. The amount of doped Lu was 0.05at%. Lu  $L_{III}$ -edge XAFS spectra were measured using fluorescence mode at the BL12C station with double Si(111) monochromator at 20K. In the curve fitting analysis, parameters of the phase shift, the back scattering amplitude and the electron mean free path were obtained using FEFF program.

### Results and discussion

Fig. 1 shows (a)  $k^3$ Lu  $L_{III}$ -edge EXAFS,  $k^3\chi(k)$ , of 0.05at%Lu- $\text{Al}_2\text{O}_3$  and  $\text{Lu}_2\text{O}_3$  as reference sample and (b) Fourier transform of them.  $F(r)$  of Lu in  $\text{Al}_2\text{O}_3$  exhibit only one peak at 1.9Å, which corresponds to the first nearest Lu-O pair, while  $\text{Lu}_2\text{O}_3$  shows long distance correlations. Such vanishing of the long distance correlation of  $F(r)$  of Lu in  $\text{Al}_2\text{O}_3$  suggests strong distortion of the local structure around Lu atoms. The results of the curve fitting analysis of the Lu-O correlation of Lu in  $\text{Al}_2\text{O}_3$  are listed in a table 1. Since, one Gaussian fitting did not converge well in this curve fitting procedure, we use double Gaussian fitting for the Lu-O peak of Lu in  $\text{Al}_2\text{O}_3$ . Mean cation-oxygen distance in the octahedral site (coordination number is six) of the  $\text{Lu}_2\text{O}_3$  is 2.24Å and that of the  $\text{Al}_2\text{O}_3$  is 1.91Å. Consequently, it can be concluded that doped Lu in  $\text{Al}_2\text{O}_3$  mainly occupy the octahedral site which similar to that in the  $\text{Lu}_2\text{O}_3$ . Larger mean coordination number of 6.5, however, suggests that Lu atoms also occupy the site with

large volume. This heterogeneity of the local structure around Lu atoms causes large Debye-Waller factor. The local structure around Lu obtained from EXAFS reflects the condensation of Lu in the grain boundary of  $\text{Al}_2\text{O}_3$ .

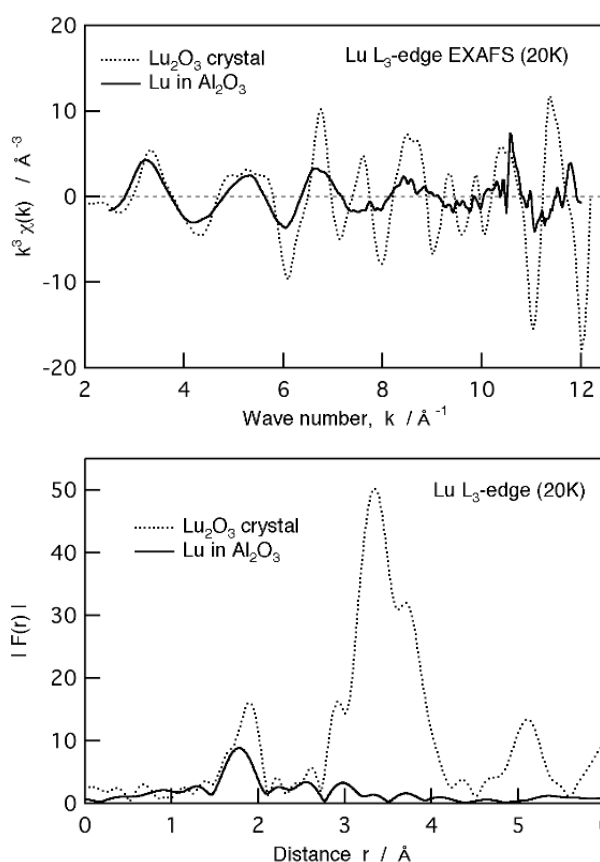


Fig.1 (a)  $k^3$  Lu  $L_{III}$ -edge EXAFS,  $k^3\chi(k)$ , of 0.05at%Lu- $\text{Al}_2\text{O}_3$  and  $\text{Lu}_2\text{O}_3$  and (b) Fourier transform of them.

Table 1: Curve fitting results for Lu-O correlation of Lu  $L_{III}$ -edge EXAFS for Lu in  $\text{Al}_2\text{O}_3$ . N, R and  $\sigma$  correspond to coordination number, atomic distance and Debye-waller factor, respectively.

	N	R(Å)	$\sigma(\text{Å})$
Lu <sub>1</sub> -O	1.3	2.02	0.06
Lu <sub>2</sub> -O	5.2	2.34	0.11

### References

[1] H. Yoshida et al., Int. J. Inorg Mater. 1, 229 (1999)

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